

<b>Notice of References Cited</b>	Application/Control No. 10/630,444	Applicant(s)/Patent Under Reexamination KOYANAGI ET AL.	
	Examiner W. David Coleman	Art Unit 2823	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Kaupo Kukli et al., "Atomic Layer Depositon and Chemical Vapor Deposition of Tantalum Oxide by Successive and Simultaneous Pulsing of Tantalum Ethoxide and Tantalum Chloride" Chemical Materials 2000, vol. 12, pp. 1914-1920, American Chemical Society
	V	
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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